

J.P.W.

Docket No.: 055071-0328

PATENT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Is/re Application of

Robert John SOCHA, et al.

Application No.: 10/756,829

Filed: January 14, 2004

For: METHOD OF OPTICAL PROXIMITY CORRECTION DESIGN FOR CONTACT HOLE MASK

: Customer Number: 20277
:
: Confirmation Number: 2388
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: Group Art Unit: 1756
:
: Examiner: Yet to be assigned
:

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Mail Stop IDS
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

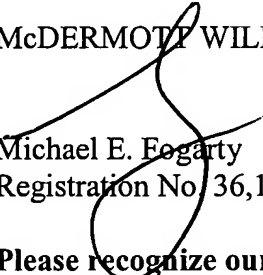
This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

10/756,829

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

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**Please recognize our Customer No. 20277
as our correspondence address.**

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

ATTY. DOCKET NO.
055071-0328

SERIAL NO.
10/756,829

APPLICANT
Robert John SOCHA, et al.

FILING DATE
January 14, 2004

**GROUP
1756**

(PTO-1449)

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		KENNY K.H. TOH, ET AL., "Design Methodology for Dark-Field Phase-Shifted Masks," SPIE Vol. 1463 Optical/Laser Microlithography IV (1991), p. 402-413.
		RICHARD SCHENKER, ET AL., "Alternating Phase Shift Masks for Contact Patterning," Proceedings of SPIE Vol. 5040 Optical Microlithography XVI (2003), p. 294-302.

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.